

ABSTRACT

A lithographic apparatus includes an illumination system for providing a beam of radiation and an article support for supporting an article to be placed in a beam path of the beam of radiation on the article support. The article support has a plurality of supporting protrusions. The plurality of protrusions define a support zone for providing a flat plane of support. A backfill gas feed is arranged in the support zone for providing a backfill gas flow to a backside of the article when supported by the article support, for providing an improved thermal conduction between the article and the article support. According to one aspect of the invention, the support zone is surrounded by a boundary zone having a reduced height relative to the plane of support so that the backfill gas flow is not bounded to the support zone.